

- BRS:
- BRS:
- Pending
- Active
 - L1: (382) ((primary and secondary) near2 beams)
 - L2: (281) 1 and accelerat\$3
 - L3: (202) 2 and separat\$3
 - L4: (185) 3 and (detect\$3 or sens\$3)
 - L5: (77) 4 and (plate same (apertures or opening))
 - L6: (27) 5 and ((primary and secondary) near2 optical)
- Failed
- Saved
- Favorites
- Tagged (0)
- UDC
- Queue
- Trash

Search: Help **Plures**

DBs: **USPAT; US-PGPUB; EPO; JPO; DERWENT** **Plures**

Default operator: **OR** **Highlight all hit terms initially**

Search results will appear here.

	Type	L#	Hits	Search Text	DBs	Time Stamp	Comments	E	Err
1	BRS	L1	382	((primary and secondary) near2 beams) and (sample or wafer or substrate or target) and (electron near (gun or source))	USPAT, US-PGPUB; EPO; JPO; DERWENT	2004/10/12 16:32		0	
2	BRS	L2	281	1 and accelerat\$3	USPAT, US-PGPUB; EPO; JPO; DERWENT	2004/10/12 16:33		0	
3	BRS	L3	202	2 and separat\$3	USPAT, US-PGPUB; EPO; JPO; DERWENT	2004/10/12 16:33		0	
4	BRS	L4	185	3 and (detect\$3 or sens\$3)	USPAT, US-PGPUB; EPO; JPO; DERWENT	2004/10/12 16:34		0	
5	BRS	L5	77	4 and (plate same (apertures or openings))	USPAT, US-PGPUB; EPO; JPO; DERWENT	2004/10/12 16:34		0	
6	BRS	L6	27	5 and ((primary and secondary) near2 optical)	USPAT, US-PGPUB; EPO; JPO; DERWENT	2004/10/12 16:35		0	

- BRS:
 - Pending
 - Active
 - L1: (3354) (electron adj beam) and gun and (sample or wafer or substrate or target) and accelerat\$3 and separat\$3
 - L2: (247) 1 and ((primary and secondary) near3 beam)
 - L3: (245) 2 and direct\$3
 - L4: (222) 3 and (detect\$3 or sens\$3)
 - L5: (137) 4 and plate and (aperture or opening)
 - L6: (35) 5 and ((primary and secondary) near2 optical)
 - L7: (130) 5 and optical
 - L8: (102) 7 and (315/\$.ccls. or 250/\$.ccls. or 438/\$.ccls.)
 - Failed
 - Saved
 - Favorites
 - Tagged (0)
 - UDC
 - Queue
 - Trash

DBs: USPAT; US-PGPUB; EPO; JPO; DERWENT

Plurals

Default operator: OR

Highlight all hit terms initially

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	E	Err
1	BRS	L1	3354	(electron adj beam) and gun and (sample or wafer or substrate or target) and accelerat\$3 and separat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:35		0	
2	BRS	L2	247	1 and ((primary and secondary) near3 beam)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:36		0	
3	BRS	L3	245	2 and direct\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:36		0	
4	BRS	L4	222	3 and (detect\$3 or sens\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:36		0	
5	BRS	L5	137	4 and plate and (aperture or opening)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:37		0	
6	BRS	L6	35	5 and ((primary and secondary) near2 optical)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:38		0	
7	BRS	L7	130	5 and optical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:38		0	
8	BRS	L8	102	7 and (315/\$.ccls. or 250/\$.ccls. or 438/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/12 09:39		0	